

TEL Formula 300mm Configuration :

Data & Configuration

Description: Diffusion (Amorphous Anneal , α -Si)

Manufacturer: TEL

Model: FORMULA

Wafer Size: 300mm

Vintage: 2009.

S/W Version 2.0

Configuration:

< Basic Configuration >

Thoroughput: 50 wafers in Batch

Temperature: 850°C

Gas Unit: PH3 1% ,F2, H2, O2 ,

System Controller: WAVES/Model780

Heater: Mid-Temp VCM-50-XXX

Exhaust Controller: CKD VEC

EXH Box: Standard Type (190 cm width)

Dry Pump: Exclude

< Gas Configuration >

Gas Pressure Flow Connection Type

Gas Box

P-N2 0.5MPa 92 L/min $\phi 1/4$ "UJR

1%PH3/He 0.2MPa 5 L/min $\phi 1/4$ "UJR

H2 0.2MPa 5 L/min $\phi 1/4$ "UJR

O2 0.2MPa 5 L/min $\phi 1/4$ "UJR

F2 0.2MPa 5 L/min $\phi 1/4$ "UJR

EXH Box

P-N2	-	-	$\phi 3/4$ "SWG
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P-N2	-	-	$\phi 1/2$ "SWG
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P-N2	-	-	$\phi 1/2$ "SWG
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D-N2 - - $\phi 3/8$ "SWG

D-N2 - - $\phi 3/8$ "SWG

D-N2 - - $\phi 1/4$ "SWG

Vacuum 20KPa - $\phi 3/8$ "SWG

RCU

P-N2 0.7MPa 1200 L/Min $\phi 3/4$ "SWG

D-N2 0.7MPa - $\phi 1/4$ "SWG

P-N2 - - $\phi 3/4$ "SWG

P-N2 - - $\phi 1/2$ "SWG

P-N2 - - $\phi 1/2$ "SWG

D-N2 - - $\phi 3/8$ "SWG

D-N2 - - $\phi 3/8$ "SWG

D-N2 - - $\phi 1/4$ "SWG

Pump

D-N2 0.7MPa - $\phi 1/4$ "SWG

D-N2 0.7MPa 110 L/min $\phi 1/2$ "SWG